

Certificate of Analysis (CoA)

Dec. 25, 2025

Product Name: Aluminum-doped Zinc Oxide (AZO) Sputtering Target

Chemical Formula: $\text{ZnO:Al}_2\text{O}_3$

Composition: 97 wt% ZnO / 3 wt% Al_2O_3

Purity: 99.99% (4N, oxide basis)

Dimensions: Ø76.2 mm × 1.59 mm

Bonding: Indium-bonded to Copper (Cu) Backing Plate, 1.59 mm thick

Lot Number: CSFM-251225085TB

Quantity: 1 piece

Manufactured by: Thin-Film Materials

Physical Description

- Form: Oxide ceramic sputtering target, bonded
- Appearance: Off-white to light gray, dense ceramic
- Crystal Structure: Hexagonal wurtzite (ZnO structure with Al doping)
- Theoretical Density: ~5.6 g/cm³
- Resistivity: < 1.0×10^{-3} Ω·cm (for sintered target)
- Fabrication: Powder synthesis, pressing, sintering, precision grinding, and bonding

Total Impurities (by ICP-OES / GDMS)

Element	Symbol	Max. Content (ppm)
$\text{ZnO, Al}_2\text{O}_3$	Zn, Al	Balance (>99.99%)
Iron	Fe	< 5
Silicon	Si	< 5
Copper	Cu	< 5
Lead	Pb	< 5
Nickel	Ni	< 5

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Element	Symbol	Max. Content (ppm)
Sodium	Na	< 5
Other Metallic (each)	-	< 2

Handling & Storage

- This is a brittle ceramic material. Handle with care to avoid chipping or cracking.
- Store in a dry, clean environment to prevent moisture absorption and contamination.
- Avoid thermal shock.

Declaration

We certify that this AZO target meets the specified doping concentration and 4N purity, providing a reliable source for depositing transparent conductive oxide (TCO) thin films in cost-effective photovoltaic, display, and low-emissivity coating applications.

Authorized Signature:

Inspection Certificate by: Nancy Liu

Approver by: Chen Qiang

